

Amendments to the Specification:

Please replace the paragraph beginning on page 10 of the specification, line 27, with the following:

FIG. 13 shows a deposited conformal oxide spacer 1301. The oxide spacer 1301 defines a width of a nitride "boot" (described infra). The nitride boot allows feature sizes in general, and the emitter -base contact region in particular, to be formed smaller than conventional photolithographic techniques allow. The oxide spacer 1301 ~~[[1302]]~~ additionally provides for self-alignment of the base-emitter region. In an exemplary embodiment, the oxide spacer 1301 is deposited using LPCVD techniques, although other deposition techniques may be used as well. Alternatively, the oxide spacer 1301 is formed using polycrystalline silicon instead of oxide.